# **RELATIVE BASICITY OF ORGANOTRIALKOXYSILANES AND ELECTRONIC EFFECTS OF SUBSTITUENTS\***

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Received December 28th, 1973

Relative basicity of organotrialkoxysilanes  $R^1Si(OR^2)_3$ , where  $R^1$  is an organic substituent and  $R^2$  is a methyl or ethyl group, was determined by IR spectroscopy. It was found that the relative basicity,  $\Delta v(OH)$ , is linearly dependent on Taft  $\sigma^*$  inductive constant of substituent  $R^1$ .

The relative basicity,  $\Delta v(OH)$ , is a parameter which is sensitive to electronic effects of substituents. In studies of alkoxysilanes<sup>1,2</sup>, alkoxygermanes<sup>2</sup>, ethinylalkoxysilanes<sup>3</sup>, and phenoxysilanes<sup>4</sup> of the type  $R_{\rm d-n}^{\rm Si}(OR^2)_{n}$  it was shown that the basicity of oxygen decreases nonlinearly with increasing number of alkoxy groups  $OR^2$  (n = 1-4). With disubstituted arylethinylphenoxysilanes<sup>4</sup>,  $\Delta v(OH)$  is linearly dependent on  $\sigma$  substituent constants characterizing electronic effects of substituent stituents attached to aromatic ring.

As known<sup>5-8</sup>, the basicity of oxygen in organic compounds of Group IVb elements (M) containing M-O linkage depends strongly on electronic effects of substituents on atom M (M = Si, Sn, and Ge). The extent of back donation in Si  $\leftarrow O$  bond is also affected by the nature of substituents on silicon<sup>9</sup>.

In the present communication the effect of substituents on silicon on the basicity of oxygen in organotrialkoxysilanes was studied. For this purpose the formation of hydrogen bond between organotrialkoxysilanes as proton acceptors and standard proton donors, phenol and pyrrole, was investigated. The shifts  $\Delta v$ (OH) of phenol and  $\Delta v$ (N—H) of pyrrole were taken as a measure of basicity. Energy of hydrogen bond was calculated on the basis of temperature dependence of equilibrium constants<sup>10</sup>.

## EXPERIMENTAL

Preparation and physico-chemical constants of starting compounds were reported earlier: n-propyltriethoxysilane<sup>2</sup>, benzyltriethoxysilane<sup>11</sup>, vinyl- and phenyltriethoxysilane<sup>12</sup>, (chloromethyl)triethoxysilane<sup>13</sup>, (2-thio-1-butyl)trimethoxysilane and (3-phenyl-2-thio-1-propyl)trimethoxysilane<sup>14</sup>, iodomethyl-, bromomethyl-, and (trichloromethyl)trimethoxysilane<sup>15</sup>.

IR spectra were recorded with a Zeiss, Model UR-20, spectrophotometer (Jena, GDR) in the 3700-3200 cm<sup>-1</sup> region (LiF prism). For each compound  $\Delta v$  value was taken as an average

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Part CXVII in the series Organosilicon Compounds; Part CXVI: This Journal 39, 1735 (1974).

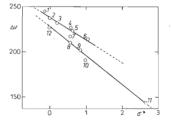
of three measurements. Wavenumbers were read with an accuracy of  $\pm 2 \text{ cm}^{-1}$ . Concentrations of proton acceptors are given in the table; phenol and pyrrole concentrations were 0.02 M and 0.015M, respectively (for  $\Delta \nu$ 's determinations). Spectrograde CCl<sub>4</sub> was used as a solvent. Infrasil cell was 1 cm thick. Temperature measurements in the 6-48°C region were made with special temperature controlled blocks.

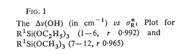
# RESULTS AND DISCUSSION

The values of  $\Delta v$  of stretching OH and NH frequencies of phenol and pyrrole, respectively, as well as Taft  $\sigma^*$  inductive constants of substituents, which were used as a quantitative measure of inductive effect, for all the organotrialkoxysilanes investigated are summarized in Table I. As follows from the table, with both proton donors, phenol and pyrrole, the basicity changes paralel changes in inductive effect of substituents. The greatest basicity was observed with alkylsubstituted compounds (1, 2) in which substituent  $\mathbb{R}^1$  is electron donating. As substituents on silicon become stronger electron acceptors, the positive charge on silicon increases. This results in an extention of Si  $\leftarrow$  O back donation which brings about a decrease in basicity of oxygen (Table I).

The lowest basicity is exhibited by compound 11 in which strongly electron-attracting CCl<sub>3</sub> group is attached to silicon. According to the earlier reported data<sup>4</sup>, the presence of phenyl and vinyl groups (compounds 4 and 5) should lead to the lower basicity, compared to the values predicted on the basis of Taft  $\sigma^*$  constants. However, the data for these compounds lie on the  $\Delta v$ (OH) vs  $\sigma^*$  plot (Fig. 1). Therefore, substituent R<sup>1</sup> affects the basicity of the oxygen in compounds 4 and 5 predominantly by its inductive effect. A linear dependence of  $\Delta v$ (OH) on  $\sigma^*$  (Fig. 1) and the values of correlation coefficients (0.992 for R<sup>1</sup>Si(OC<sub>2</sub>H<sub>5</sub>)<sub>3</sub>; 0.965 for R<sup>1</sup>Si(OCH<sub>3</sub>)<sub>3</sub> further indicate that the electronic effects are transferred through silicon by inductive mechanism.

As indicated by the slopes of the above plot, calculated by the least squares method<sup>17</sup>, for series of triorganoethoxysilanes<sup>8</sup>  $(-61\cdot3)$ , organotriethoxysilanes





## TABLE I

No 1	R <sup>1</sup>	R <sup>2</sup>	Солс., м	Δν phenol pyrrole		σ*
				2	CH <sub>3</sub>	$C_2H_5$
3	C <sub>6</sub> H <sub>5</sub> CH <sub>2</sub>	$C_2H_5$	0.19	232	112	0.23
4	CH2=CH	$\tilde{C_2H_5}$	0.16	227	113	0.59
5	$C_6 \tilde{H}_5$	$\tilde{C_2H_5}$	0.54	224	110	0.62
6	CICH <sub>2</sub>	$\tilde{C_2H_5}$	0.98	214	92	1.05
7	C <sub>2</sub> H <sub>5</sub> SCH <sub>2</sub>	CH <sub>3</sub>	0.36	216	98	0·57°
8	C6H5CH2SCH2	CH <sub>3</sub>	0.52	211	94	0·57°
9	ICH <sub>2</sub>	CH	1.37	202	85	0.85
10	BrCH <sub>2</sub>	CH <sub>3</sub>	1.63	191	80	1.00
11	CCl <sub>3</sub>	CH <sub>3</sub>	1.35	144	53	2.65
12	CH <sub>3</sub>	CH <sub>3</sub>	_	226 <sup>d</sup>		0.00

Wavenumber Shifts,  $\Delta\nu$  (cm  $^{-1}),$  of Organoalkoxysilanes  $R^1Si(OR^2)_3$  and  $\sigma^*$  Constants of Substituents  $R^1$ 

<sup>*a*</sup> Taken from ref.<sup>2</sup>, <sup>*b*</sup> Taken from ref.<sup>1</sup>, <sup>*c*</sup> Calculated according to the relation  $\sigma_1 = \sigma^*/6.23$ ;  $\sigma_1$  was determined from pK<sub>a</sub> of aliphatic acids<sup>16</sup>. <sup>*d*</sup> Taken from ref.<sup>3</sup>.

(-24.7), and organotrimethoxysilanes (-31.8), the transmission of electronic effects through silicon depends strongly on the structure of the compounds. For the results of previous study<sup>2</sup> of series  $R_{4-n}M(OC_2H_5)_n$  (M = C, Si, Ge; n = 1-4) the interpretation was used that due to the  $(p \rightarrow d)\pi$  interaction in silicon derivatives the slope of the  $\Delta v s n$  plot is lower than in the case of carbon and germanium analogues in which the interaction between atom M and oxygen is absent or very weak. The fact that the extent to which inductive effects of substituents are transferred through silicon decreases with increasing number of alkoxy groups was established also in a <sup>1</sup>HNMR study of series<sup>18</sup>  $R_nSi(OC_2H_5)_{4-n}$ .

The difference between the slopes for organotrimethoxysilanes and organotriethoxysilane is probably due to the stronger electron-donating effect of ethyl group. The effect of substituents in both series can be described by the following regression equations:

$$\Delta \nu(OH) = 237 - 24.7\sigma^* \text{ for } R^1 \text{Si}(OC_2H_5)_3, \text{ and}$$
$$\Delta \nu(OH) = 226 - 31.8\sigma^* \text{ for } R^1 \text{Si}(OCH_3)_3.$$

Collection Czechoslov. Chem. Commun. (Vol. 39) (1974)

As in our case substituent R<sup>1</sup> affects the hydrogen bond energy very little, an attempt was made to estimate this energy only for compound 4. From temperature meas urements and calculations of thermodynamics parameters according to the kn own method<sup>10</sup>, the hydrogen bond energy was found to be approximately 3.6 kcal/mol.

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Translated by J. Hetflejš,